

### ABSTRACT

An optical inspection system and method which uses a procedure for determining an offset between a field of view and a center or rotation of an R-theta stage, or polar coordinate stage. Determining this offset allows the precise location of a site being inspected on a wafer to be determined. The system and method take advantage of the fact that in a R-theta system there can be only two positions for the R-theta stage that will position a particular site under the lens of the imaging system of the optical inspection system. By moving the stage from a first position where a particular site is positioned in the field of view, to the second position where the particular site is positioned in the field of view, the offset can be determined.